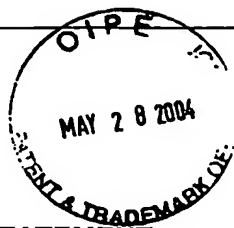


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306640

P-0390.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: DIERICHS et al.

Appln. No.: 10/719,009

Filing Date: November 24, 2003

Date: May 28, 2004

Page

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Examiner: NOT
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Group Art Unit: 2874

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Examiner

/John McPherson/

Date Considered:

06/21/2006

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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| Applicant: DIERICHS et al. | |
| Appln. No.: TO BE ASSIGNED | |
| Filing Date: November 24, 2003 | |
| Examiner: | Group Art Unit: |

Date: November 24, 2003 Page 1 of 1

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